Atty. Docket No.: 622743770 Serial No.: 08/928,652 Form PTO-1449 U.S. Department of Commerce Patent & Trademark Office Applicants: Hans BRAENDLE et al. INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary) Group Filing Date: September 12, 1998 U.S. PATENT DOCUMENTS Sub-Class Class Filing Date (if appropriate) Document Number Date Examiner Initial AA AB AC AD Æ AF AG AΗ AΤ ΑJ FOREIGN PATENT DOCUMENTS Translation Yes | No Sub-class Class Date Country Document 69PL EPO AΚ 0 701 982 A1 EBX. AL0 448 720 Al EPO 3PR AM 08-209335 Japan AN AO AΡ OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.) Average Energy Deposited Per Atom: A Universal Parameter For Describing Ion-Assisted Film Growth; Petrov et al.; Applied Physics Letters, July 5, 1993, pp. 36-38 AO Titanium Aluminum Nitride Films: A New Alternative to TiN Coatings; Muenz; Journal Of Vacuum Science & Technology, Nov.-Dec. 1986, pp. 2717-2225 AR Interrelationship Between Processing, Coating Properties And Functional Properties of Steered ARC Physically Vapour Deposited (Ti,Al)N And (Ti,Nb)N Coatings; Roos et al.; Elsevier Sequola; December 1, 1990; pp.547-556 AS DATE CONSIDERED EXAMINER Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication. EXAMINER:

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